



SWTEST

PROBE TODAY, FOR TOMORROW

2023 CONFERENCE

High Heat Dissipation: Facing New Challenges with High-Power Testing at the Wafer Level



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Overview

- **Background**
- **Industry capability with high-heat dissipation**
- **Additional considerations**
- **Conclusions**

Background

The Micron Memory Market


Memory

Storage




GDDR6X

Graphics and
ultra-bandwidth
solutions




LPDDR5

DRAM




uMCP5

Multichip
packages
(DRAM + NAND)



Solid-state drives



UFS 3.1

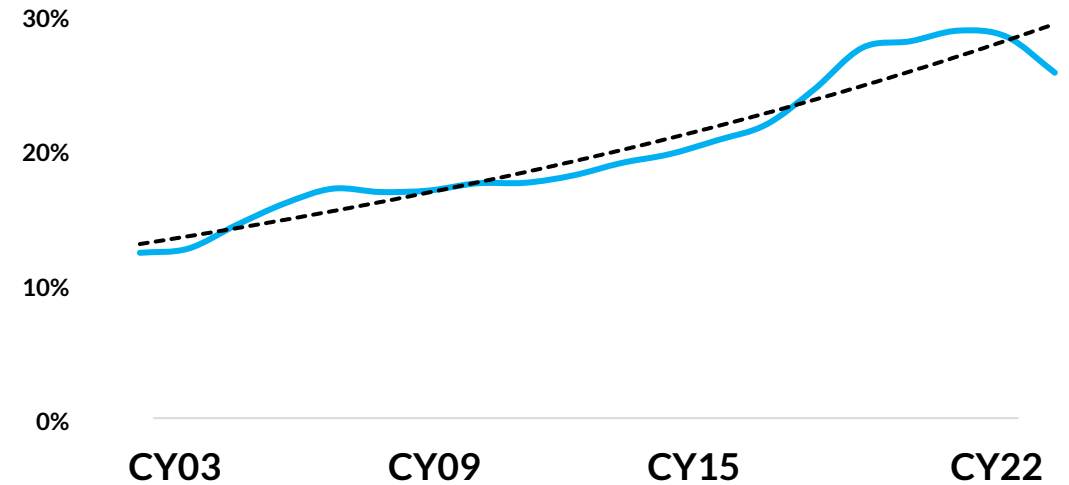
Flash storage
(NAND and NOR)

- Micron's product portfolio requires a high variety of testing requirements & conditions.

Memory Market Growth



DRAM + NAND revenue as % of semiconductor total available market
4-year moving average

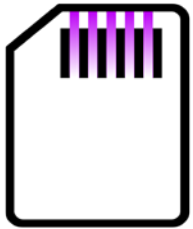


Sources: WSTS and Micron estimates

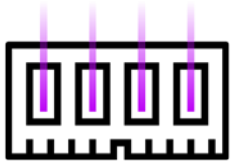
- Record memory & storage market growth by CY25 and beyond.

How do these trends affect Probe?

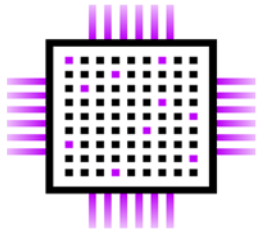
Effect on wafer fabrication



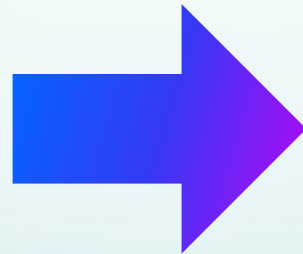
Bit density ↑



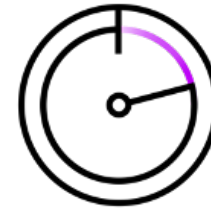
Die per wafer ↑



Die stacking & CoW +



Subsequent effect on probe



Test time ↑



Power requirements for DUTs ↑



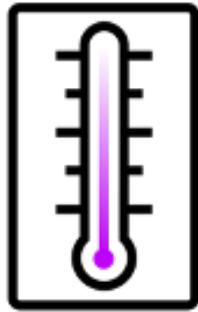
Parallelism ↑

How do these trends affect Probe?

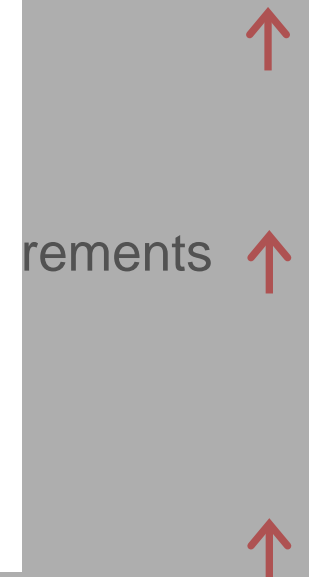
Affect on probe fabrication

Subsequent effect on probe

What do these effects on Probe lead to?



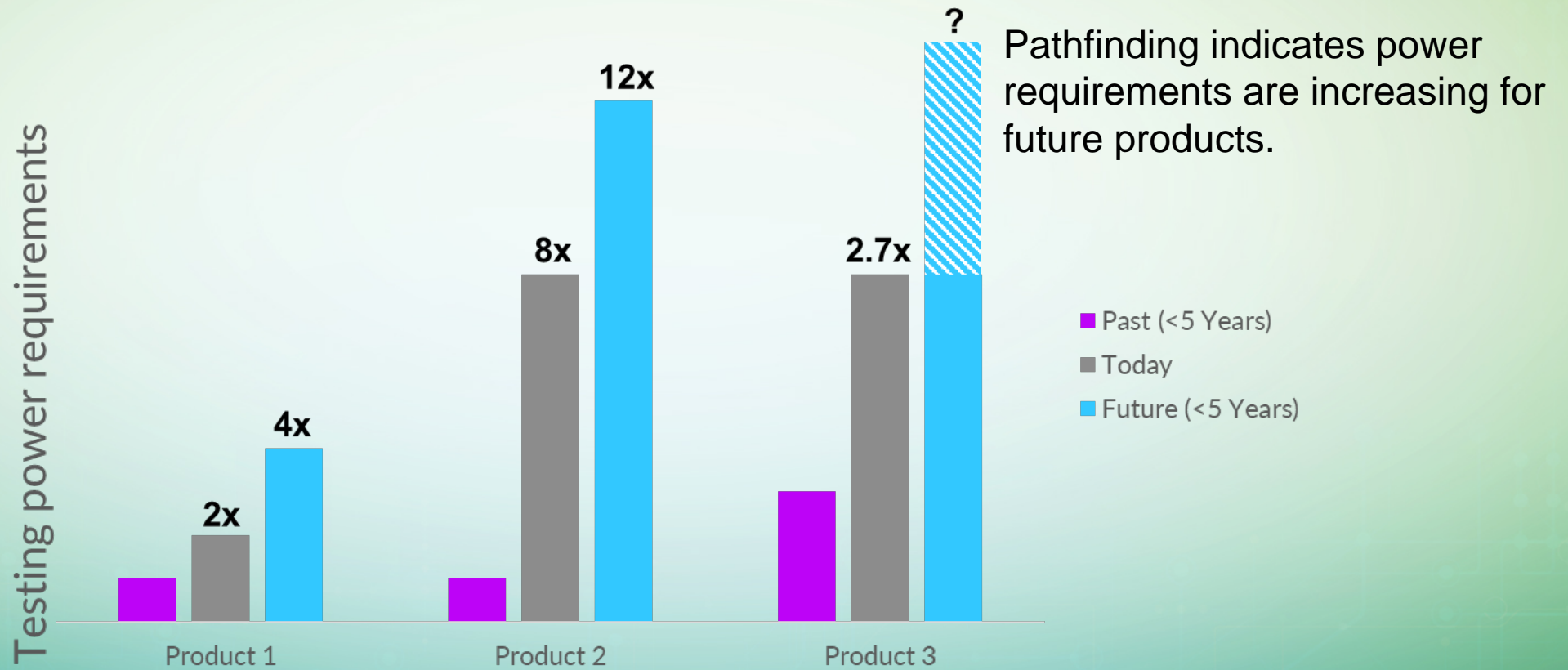
Heat dissipation requirements



requirements

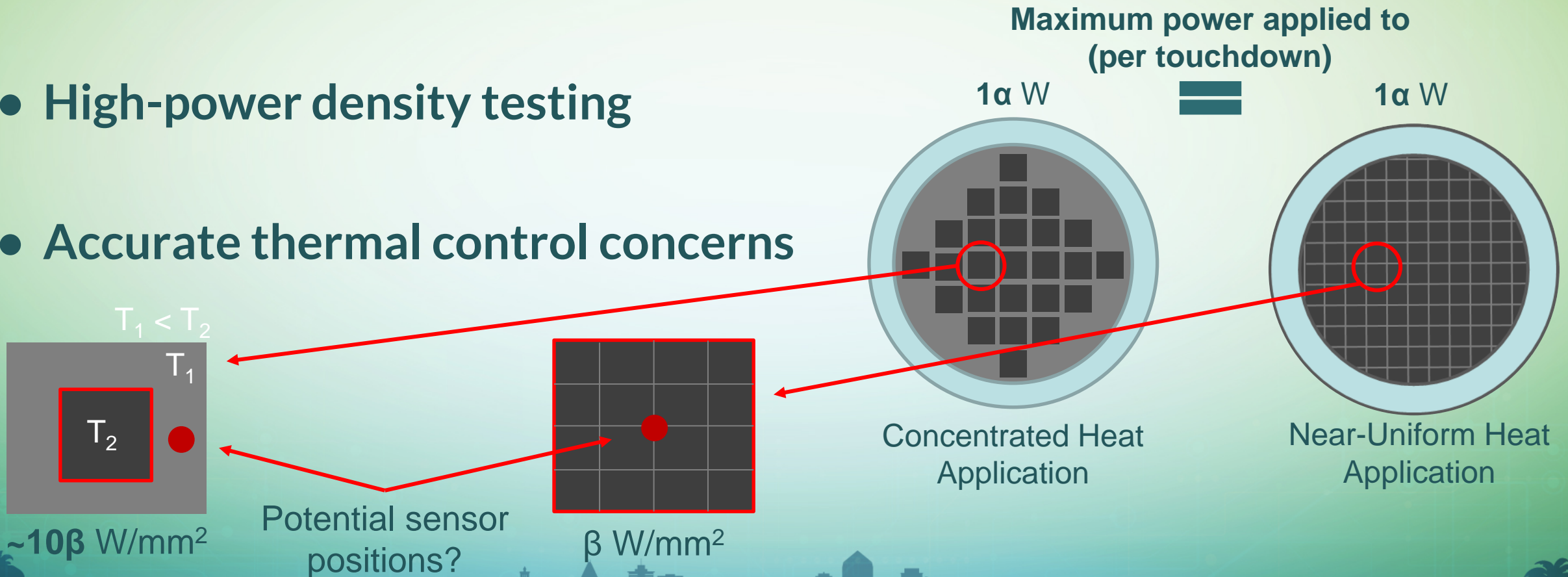
Micron power requirement forecast

- Expect to see continued increases in required testing power.



What makes memory different?

- Explosion in memory testing conditions & requirements
- High-power density testing
- Accurate thermal control concerns



Industry advancements needed

- Prober thermal control methods for high-heat dissipation must improve to meet the predicted testing power requirements.
 - Improved transient temperature response to high-power testing.
 - Decreased reliance on HTF's or creative alternative solutions.
- Investigations into removing excess probe card heat, either generated or added from the surrounding environment.

Industry capability with high-heat dissipation

Basic heat dissipation process in probe

- Energy transfer in a typical coolant-based probe system

Heat Transfer from DUTs

1. Wafer to Chuck

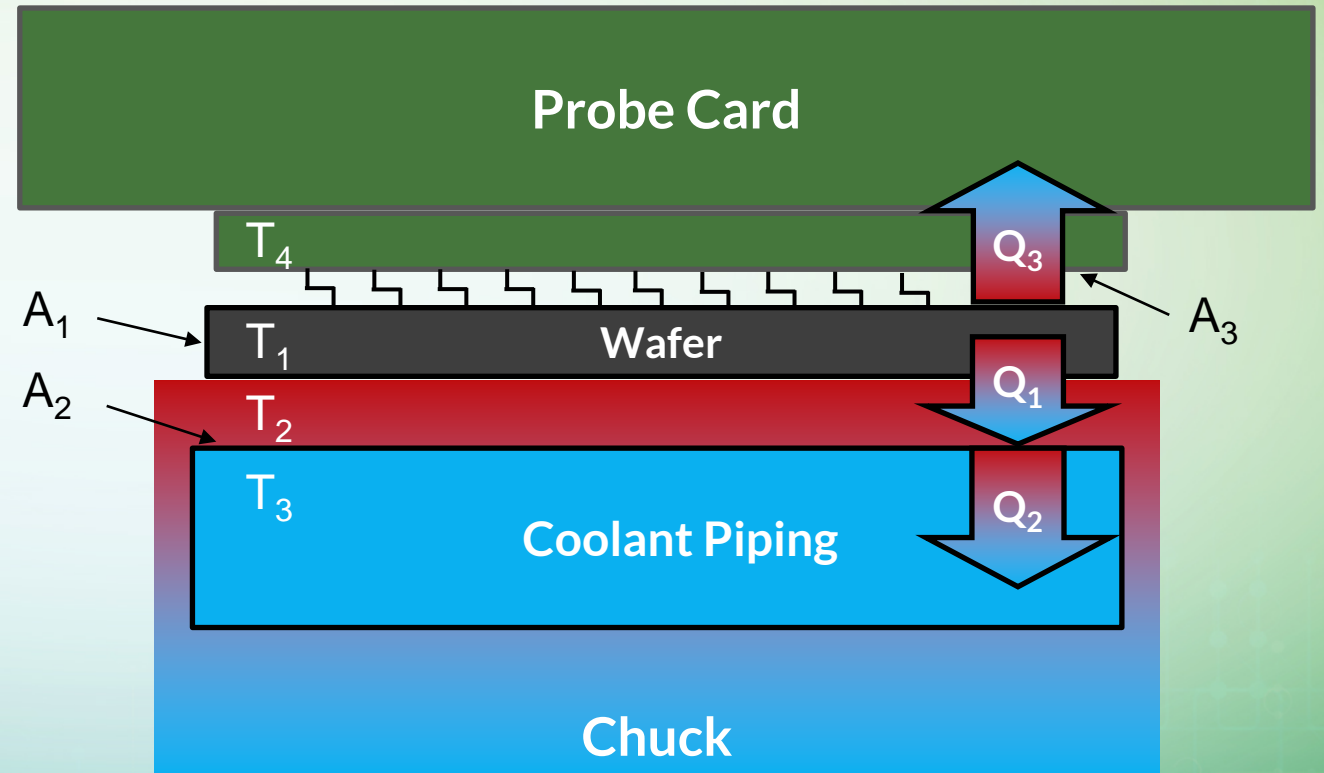
$$Q_1 = \frac{k A_1 (T_1 - T_2)}{d_1}$$

2. Chuck to Coolant

$$Q_2 = H_C A_2 (T_2 - T_3)$$

3. Wafer to Probe Card

$$Q_3 = \frac{k A_3 (T_1 - T_4)}{d_2}$$



k = thermal conductivity

H_C = conv. heat transfer coefficient

d_1 = distance between wafer & coolant

d_2 = distance between wafer & PC

A_1 = surface area of wafer

A_2 = surface area of coolant piping

A_3 = surface area of probe card

T_x = Temperature

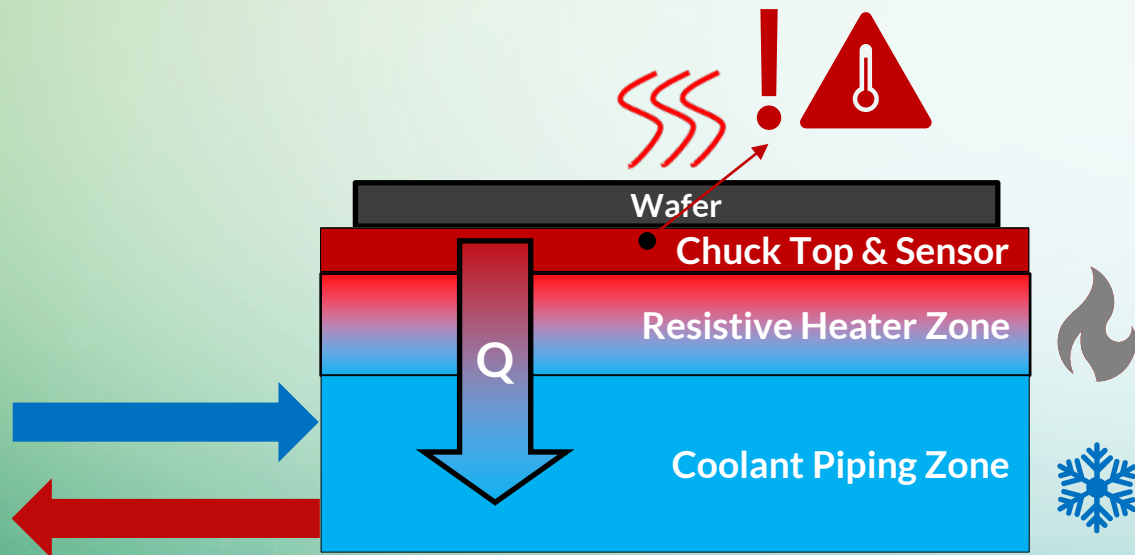
Industry thermal control systems

Continuous coolant flow

- Undercooling process
- Heater modulation for thermal control

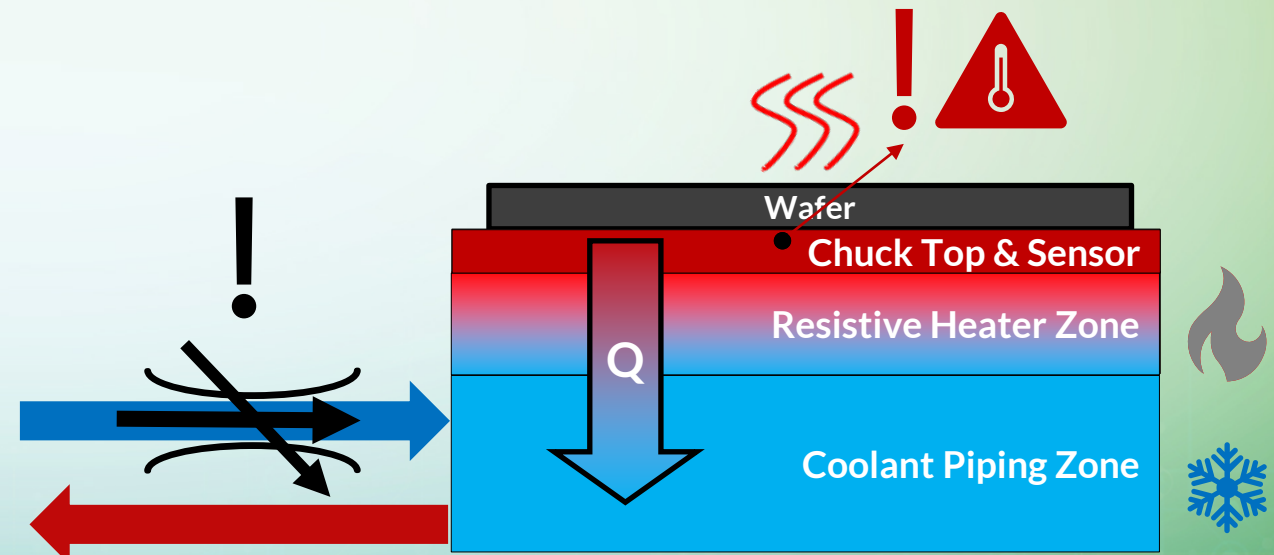
Variable coolant flow

- Heater & cooling element balancing
- High fluid temperature differential



$$Q_{CPZ} = Q_{RHZ} \rightarrow Q_{CPZ} = \downarrow Q_{RH} + Q_W$$

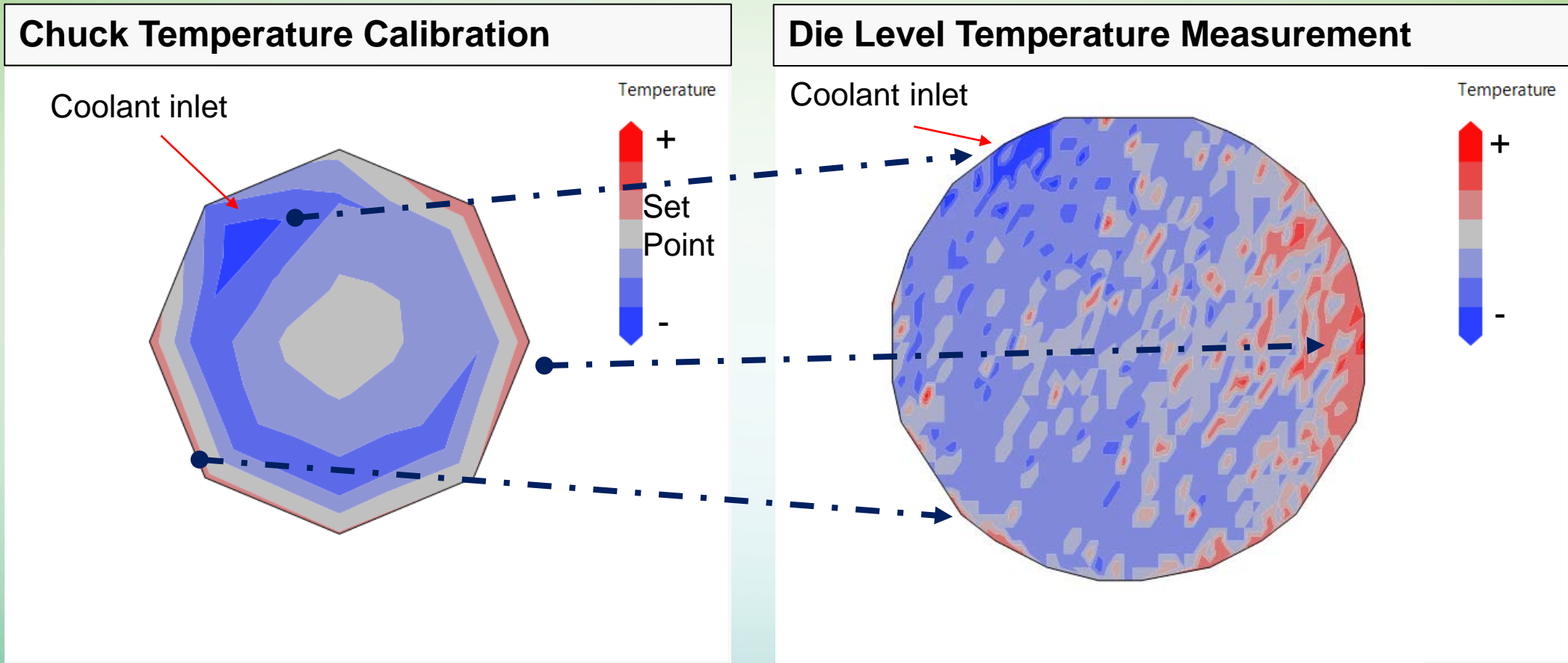
$$Q_{Static} = Q_{Test}$$



$$Q_{CPZ} = Q_{RHZ} \rightarrow \uparrow Q_{CPZ} = \downarrow Q_{RH} + Q_W$$

$$Q_{Static} \neq Q_{Test}$$

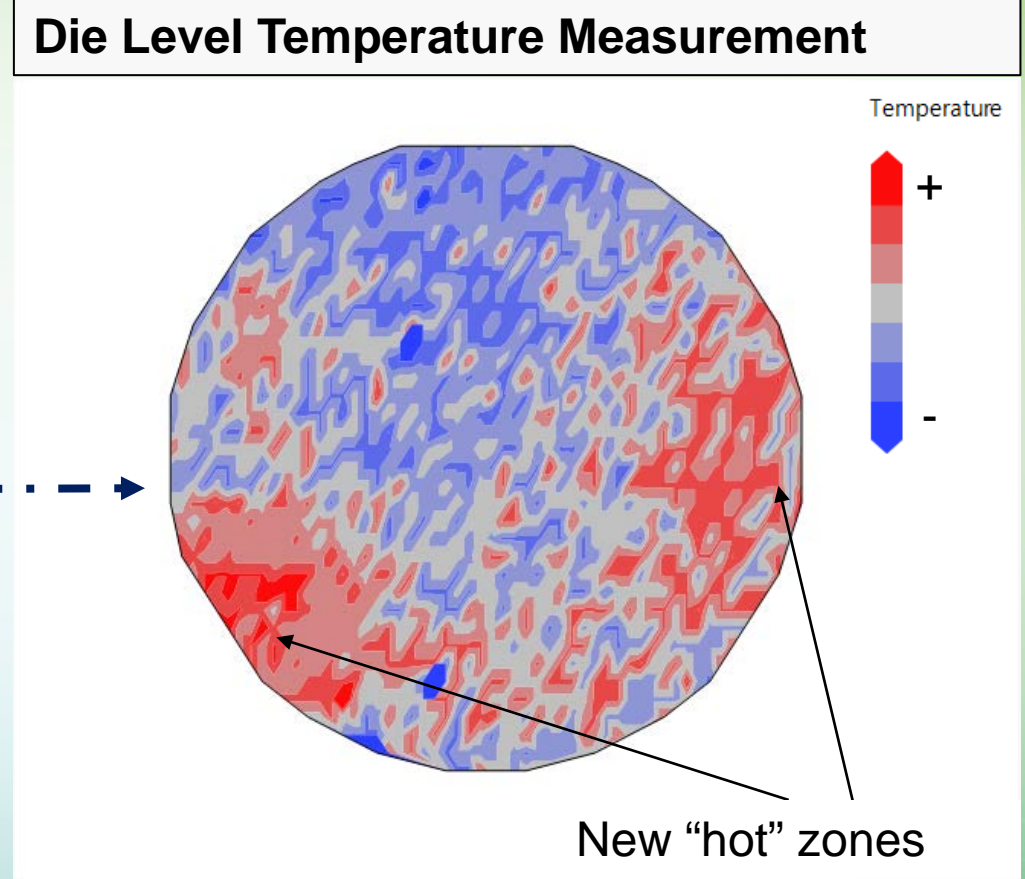
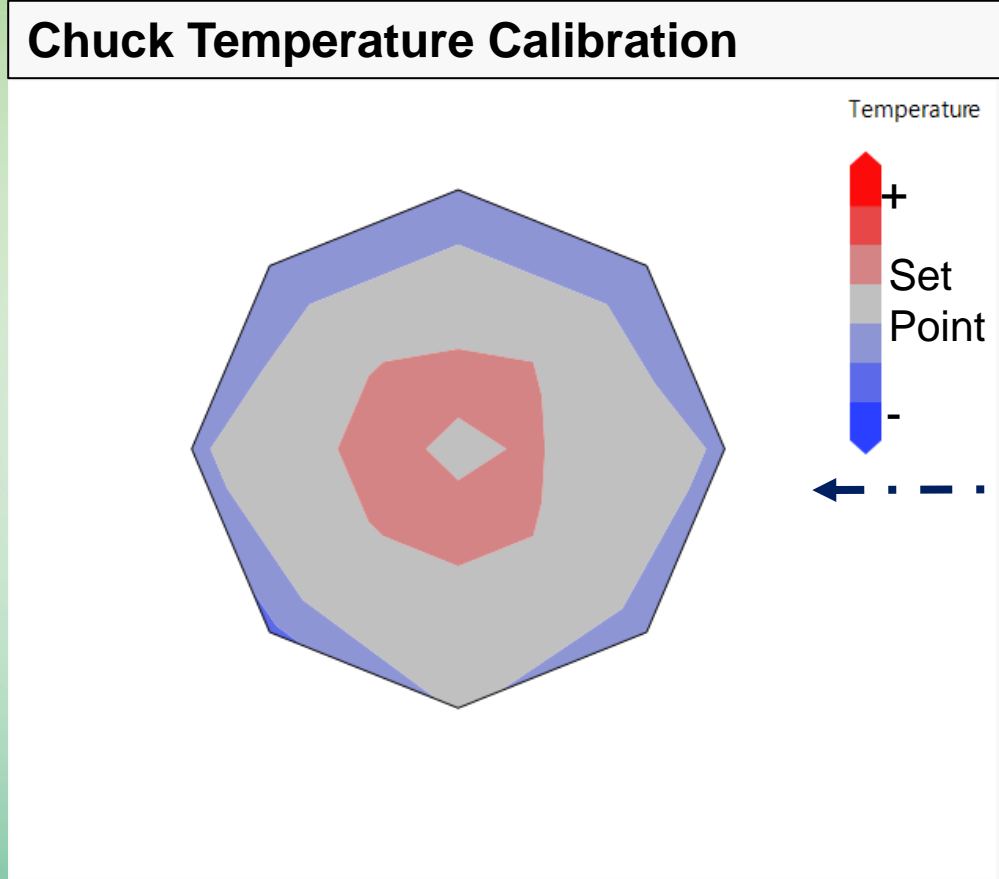
Continuous coolant flow uniformity



- Chuck uniformity is at the edge of our maximum specification.
- Similar temperature patterns between chuck calibration data and wafer level

test.

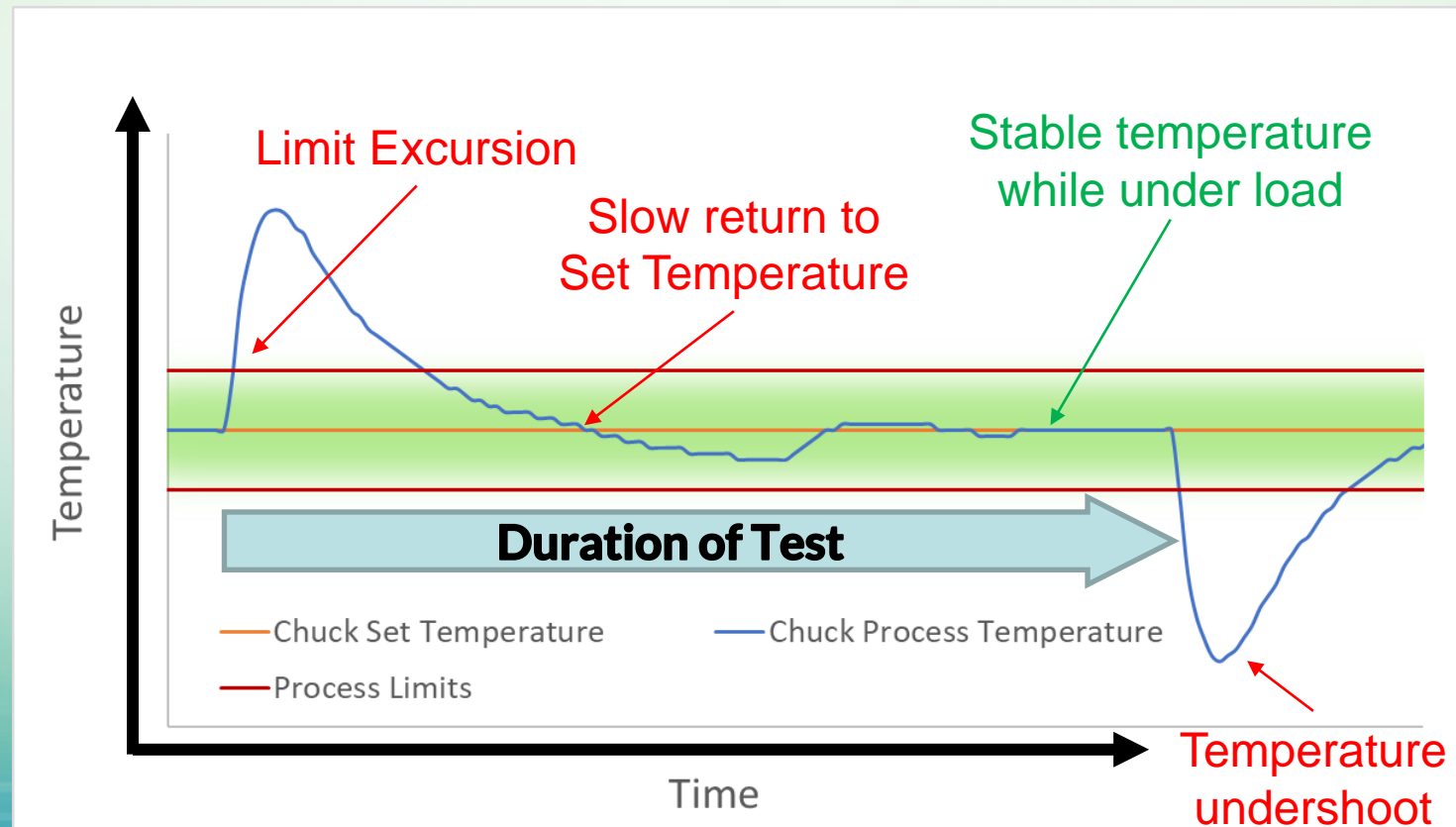
Variable coolant flow uniformity



- Stable chuck temperature uniformity is well within specification.
- Wafer level temperature testing indicate little correlation with calibration data.

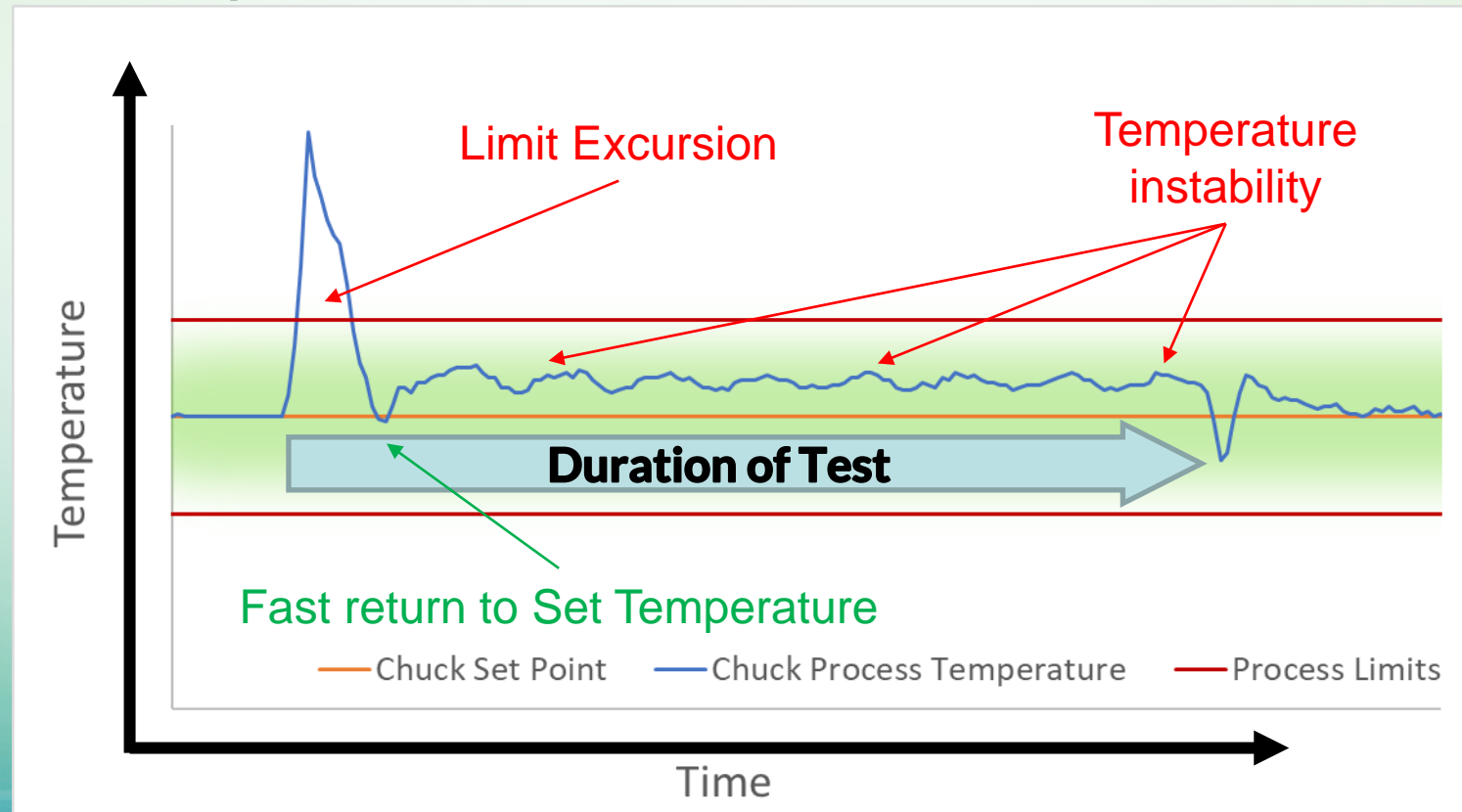
High-heat dissipation testing - Hot

- Continuous coolant flow
 - Slow response time to heat application
 - Stable after reaching set point



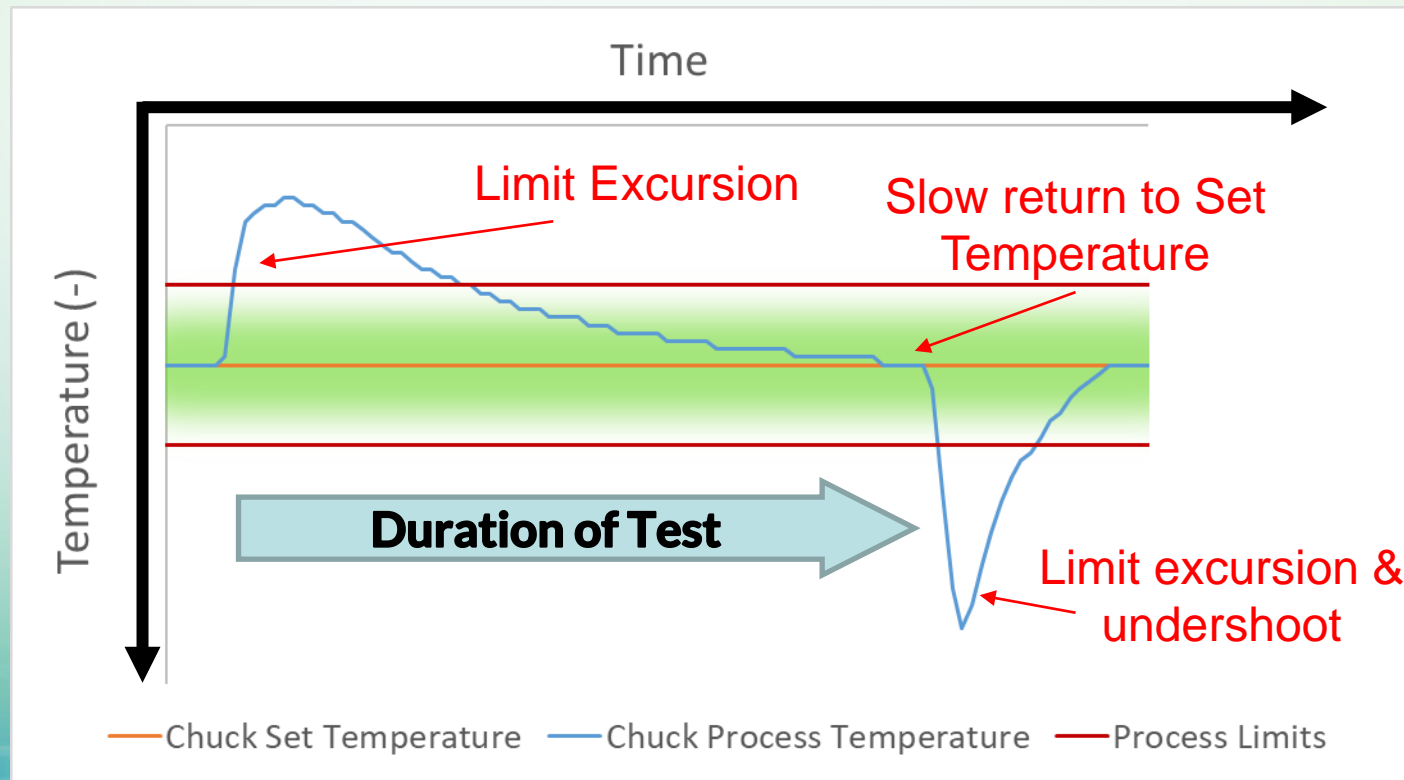
High-heat dissipation testing - Hot

- Variable coolant flow
 - Fast reaction time to high-power loading
 - Thermal instability after initial reaction



High-heat dissipation testing – Cold

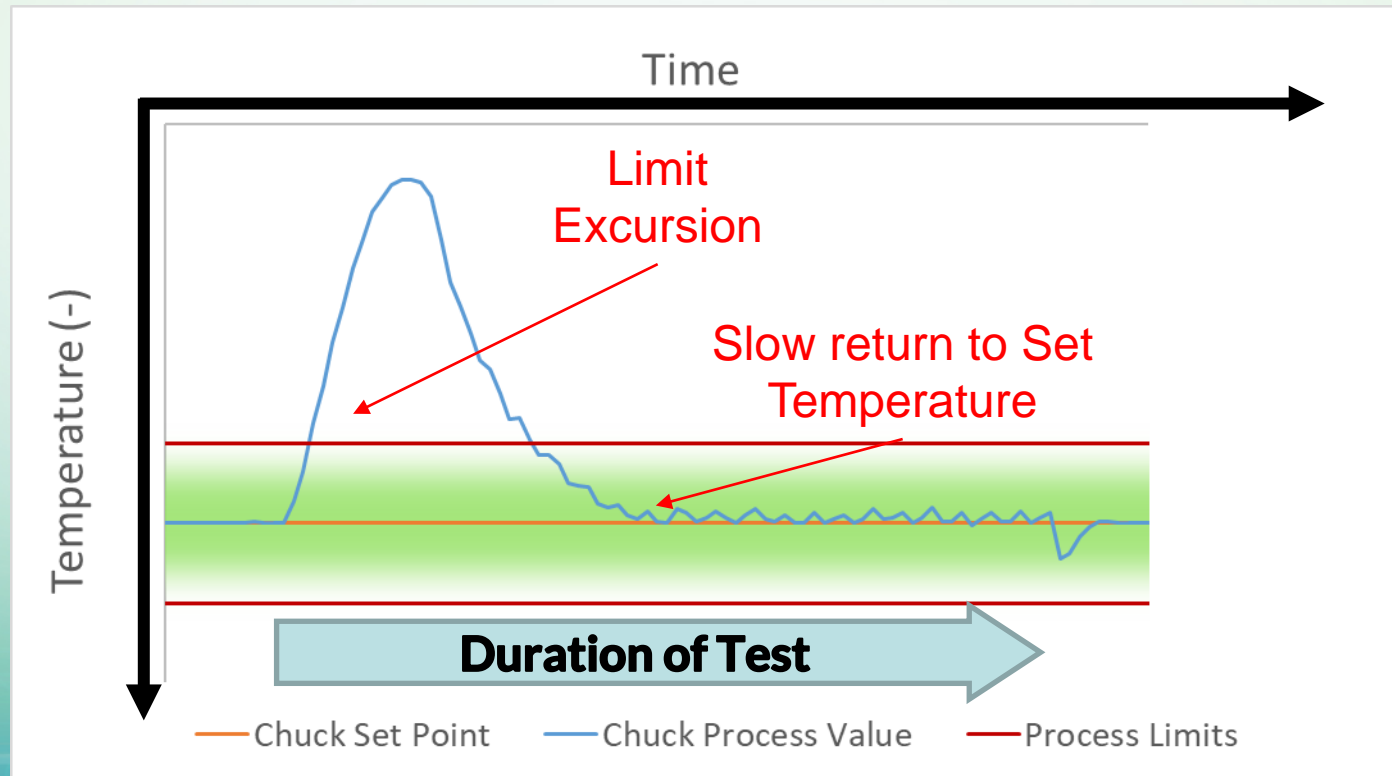
- Continuous coolant flow
 - Slow response time to heat application
 - Large temperature undershoot



High-heat dissipation testing – Cold

- Variable coolant flow

- High temperature spike during heat application
- Slow response time to heat application



Industry performance results

Performance Specification	Continuous Coolant Flow	Variable Coolant Flow	Micron's Requirements
High-heat dissipation capability	✓	✓	🎯
No process limit excursions	✗	✗	🎯
Chuck uniformity during low-power testing	!	✓	🎯
Chuck uniformity during high-power testing	!	✗	🎯
Flexibility with HTF options	✗	✓	🎯
Fast reaction time to applied power loads	✗	✓	🎯
Temperature stability during test	✓	✗	🎯

- Current industry solutions do not meet all our needs.

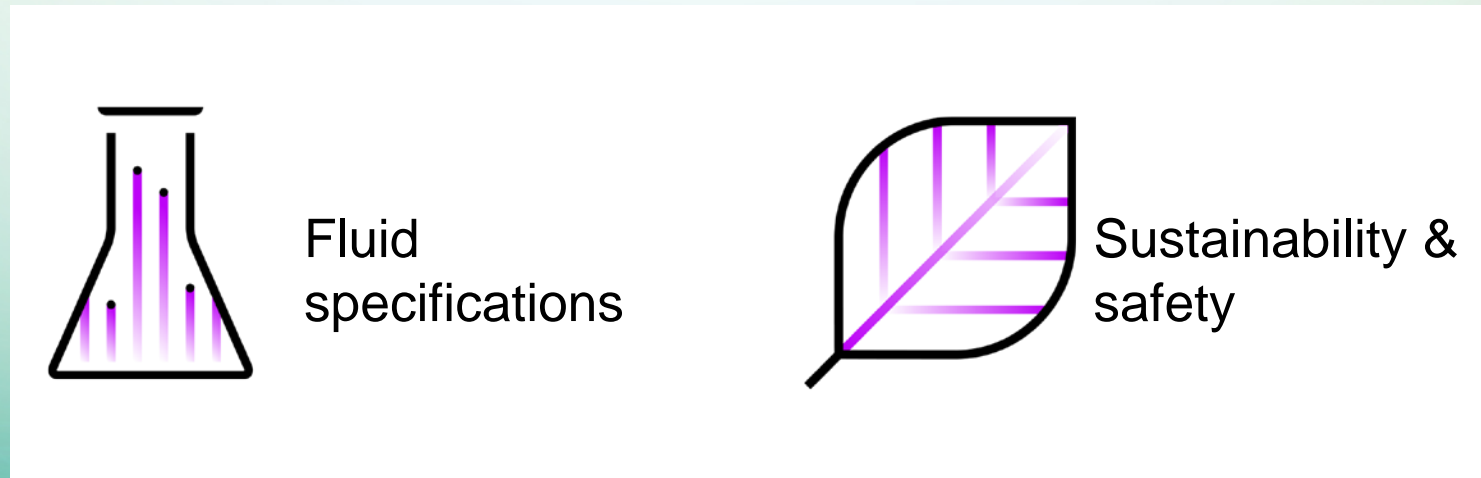
Additional considerations

Heat transfer fluid (HTF) challenges

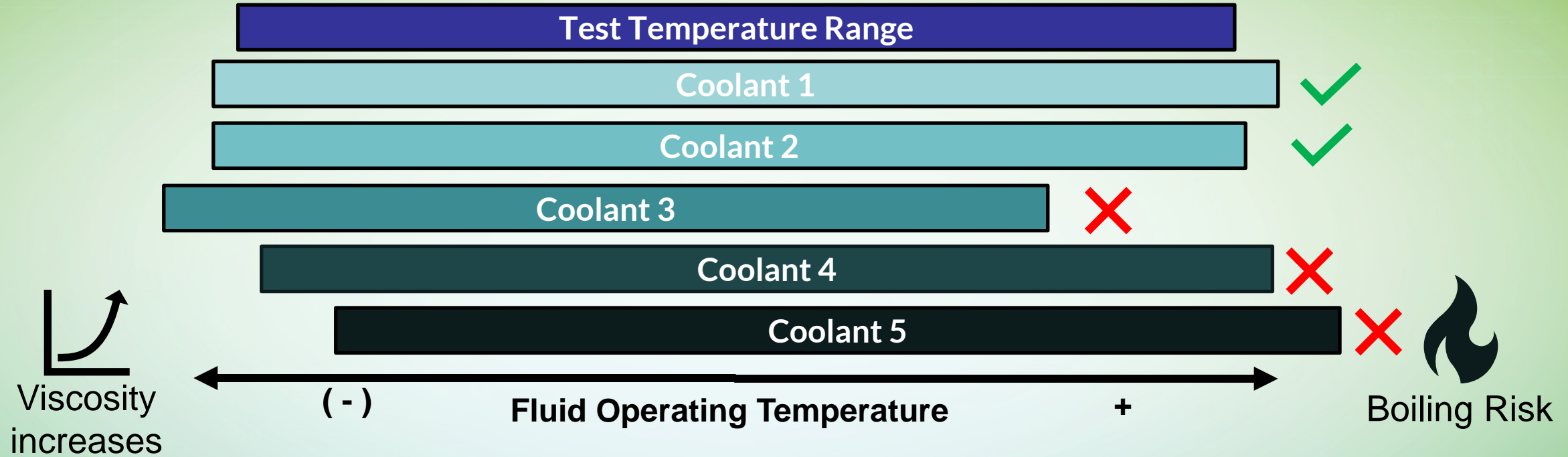
- What is the HTF role in high-power testing?

$$Q = \underline{H_c} A \underline{(T_2 - T_1)}$$

- What main factors are considered for HTF selection?



Fluid specifications



- HTF solutions that match the required test range are limited.

Environmental sustainability & safety

- Limiting global warming potential
- Per- and polyfluoroalkyl substances (PFAS) elimination
- Flash point & flammability risk

Our environmental targets

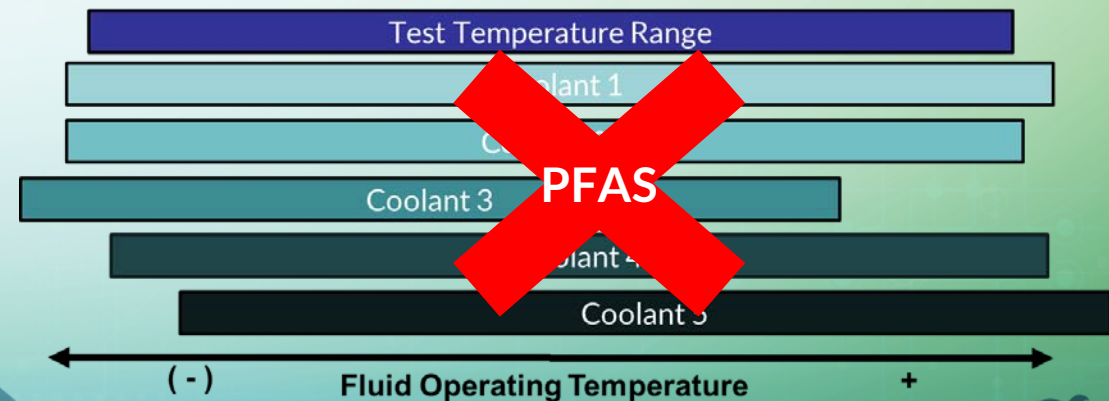
Emissions

42%

absolute reduction in scope 1 emissions by CY30 from CY20 baseline

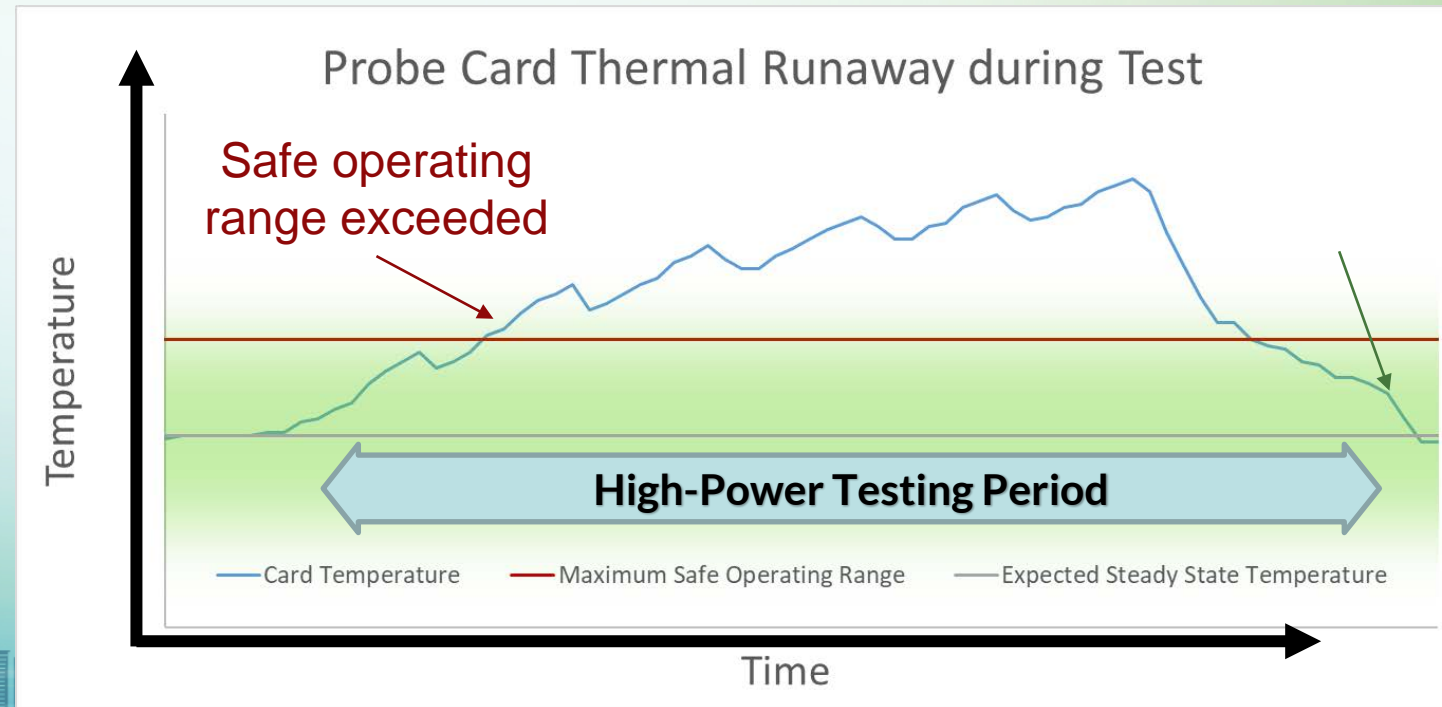
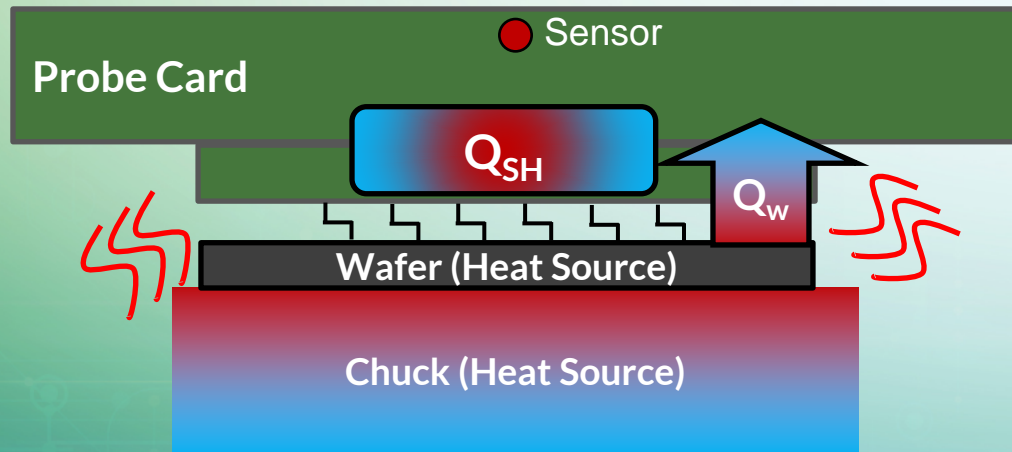
Net zero

scope 1 and 2 emissions by CY50



High-power testing & probe cards?

- High-power testing is increasing card temperatures above their design specification.
- Primary cause of temperature gain and how to remove under consideration.



Conclusions

Summary

- **Current industry thermal control methods display high-heat dissipation capability but do not meet all our requirements.**
- **Memory testing trends indicate that high-power testing has overtaken current industry high-heat dissipation capabilities.**
- **Probe card thermal management is a concern as testing power requirements will continually increase.**

Thank you!

Acknowledgements:

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